Dissolution Inhibitors for 157 nm Photolithography



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Novolac/DNQ Photoresists





Meyerhofer Plot



Functional Group Inhibition Study



PNBHFA has an absorbances of 1.14 μ m⁻¹ at 157 nm



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Absorbance vs wt% TDQ in PNBHFA



TDQ is too opaque for at 157 nm



Meyerhofer Plot of Bis-Boc Bisphenol A with 1 wt% TPSNf



248nm Exposure





133nm thick



240nm



Synthesis of a transparent *tert*-Butyl Carbonate Based DI for 157 nm





85% NBHFA + 15% 1,3 Bis Boc 157nm Exposure 100nm Cross section



PAB: 90C/60s PEB: 80C/90s DEV:20s LDD26 1840 A 18.6 mJ/cm²



Meyerhofer Plot of New DI in PNBHFA + 1 wt% TPSNf



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Meyerhofer Plot of TPSNf



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Triphenyl Sulphonium PAG With Different Counter Ions



Nonaflates With Different PAGs



Synthesis of PAGs with Better Contrast



Crivello, J. V., Lam, J. H. W. J. Org. Chem., Vol. 43, No. 15, **1978**, 3055-30058. Schwalm, R. et all. J. Chem. Soc. Perkin Trans 2. **1991**, 1803-1808.

Synthesis of PAGs with Better Contrast









Conclusions

Three component system design shows great promise

- Backwards compatibility to 193 and 248!!
- Ease of formulation should speed development

Two component system with PAGs acting as DIs is possible

- All PAGs tested effected the dissolution rate of PNBHFA and Novolac
- Slight structural modifications can greatly effect dissolution inhibition properties of PAGs



Future Work

- Continue work on DIs for 3 component system
- Test dissolution inhibition of other commercial PAGs
- Synthesis and test functionalized PAGs

Gas Phase Absorbance Data



•Surprising transparency of sulfur compounds



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